

IN THE CLAIMS:

Claim 1 (original): A vacuum treatment installation, comprising: a vacuum treatment chamber (1); a plasma discharge configuration in the chamber; as a gas supply configuration connected to the chamber; the plasma discharge configuration having at least two plasma beam discharge configurations (5, 9) with substantially parallel discharge axes (A) and at least one deposition configuration positioned along a surface (13) which extends at selected distances from the beam axes (A) and along a substantial section of the discharge beam longitudinal extension; a gas suction configuration connected to the chamber; the gas supply configuration (15) and the gas suction configuration (17) being connected to the vacuum chamber (1) such that a gas flow (G) through the chamber (1) is generated, which is substantially parallel to the discharge axes (A), and the deposition configuration is disposed between the discharge axes and/or the discharge axes (A) are disposed between two deposition configurations facing one another.

Claim 2 (original): An installation as claimed in claim 1, wherein at least one deposition configuration is formed by a workpiece support configuration for one or several workpieces (13a).

Claim 3 (original): An installation as claimed in claim 1, wherein at least one deposition configuration is formed by a substantially continuous planar configuration as a powder capture surface.

Claim 4 (currently amended): An installation as claimed in claim 1, wherein the plasma beam discharge configurations include plasma beam discharge gaps between a cathode (5) and an anode (9) of each plasma beam discharge configuration, that are low-voltage high-current arc discharge gaps.

Claim 5 (original): An installation as claimed in claim 4, wherein the gaps are driveable independently of one another.

Claim 6 (original): An installation as claimed in claim 5, wherein gaps are cold cathodes.

Claim 7 (original): An installation as claimed in claim 5, wherein gaps are hot cathodes (5).

Claim 8 (original): An installation as claimed in claim 1, wherein the gas supply configuration (15) is connected to a gas tank configuration containing at least one of a carbon-, boron-, nitrogen-, hydrogen- or silicon-containing gas.